



SMALL-SCALE INSTALLATION FOR FILM DEPOSITION BY MAGNETRON SPUTTERING

MVU TM MAGNA 05

Purpose:

Deposition of metal films and resistive materials by magnetron sputtering.

Special characteristics:

- Type and quantity of magnetron sputtering device in the installation:
DC magnetron sputtering device - 1 pcs.
- Substrate processing in one technological cycle (double-sided processing):
60 x 48 mm – 6 pcs.;
- Microprocessing control system;
- Oil-free pumping system (turbomolecular pump 300 l/h);
- Consumed power not more than 4,5 kW;
- 2,5 m² area per one installation.

